

Title (en)

DEVICE AND METHOD FOR PRODUCING LAYERS WITH IMPROVED UNIFORMITY IN COATING SYSTEMS WITH HORIZONTALLY ROTATING SUBSTRATE GUIDING

Title (de)

VORRICHTUNG UND VERFAHREN ZUR HERSTELLUNG VON SCHICHTEN MIT VERBESSERTER UNIFORMITÄT BEI BESCHICHTUNGSANLAGEN MIT HORIZONTAL ROTIERENDER SUBSTRATFÜHRUNG

Title (fr)

DISPOSITIF ET PROCÉDÉ POUR PRODUIRE DES COUCHES PRÉSENTANT UNE MEILLEURE UNIFORMITÉ DANS DES INSTALLATIONS DE REVÊTEMENT COMPRENANT UN GUIDAGE ROTATIF HORIZONTAL DU SUBSTRAT

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Application

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Abstract (en)

[origin: WO2020030794A1] The invention relates to a device and a method for producing layers with very good uniformity in coating systems with horizontally rotating substrate guiding. Alternatively, certain layer thickness gradients can be set. The particle loading is also significantly reduced. The service life is much higher compared to other methods. Parasitic coatings are reduced. The coating rate is also increased.

IPC 8 full level

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